

EXAMINER'S AMENDMENT

1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Fang Liu on May 31, 2011.

The application has been amended as follows:

2. **Claim 30** is rewritten as:

- - A polarizing plate comprising ~~[[an]]~~ the antireflection film of claim 70. - -.

3. **Claim 40** is rewritten as:

- - A method for producing a polarizing plate ~~of claim 30~~, which comprises: feeding a polymer film for a polarizing sheet; holding each edge of the polymer film with a holding unit; and stretching the polymer film by imparting a tension to the polymer film while moving the holding unit in a machine direction of the polymer film wherein the stretching is performed under a condition satisfying formula (III):

$$|L2 - L1| > 0.4W$$

wherein L1 indicates a locus of the first holding unit from a substantial holding start point to a substantial holding release point on one edge of the polymer film; L2 indicates a locus of the second holding unit from a substantial holding start point to a substantial holding release point on the other edge of the polymer film; and W indicates a distance

between two substantial holding release points of the first holding unit and the second holding unit, and a speed difference of the moving between the first holding unit and the second holding unit is less than 1% , forming a polarizing plate comprising the antireflection film of claim 70. - - .

4. **Claim 42** is rewritten as:

- - The method for producing a polarizing plate as claimed in claim 40, which comprises sticking a transparent protective film to one side of the polarizing sheet, the protective film having the antireflection film. - - .

5. **Claim 43** is rewritten as:

- - An image display comprising the antireflection film of claim 70. - - .

6. On **Page 1** of the Specification, new line:

- - This application is a 371 of PCT/JP04/19752 filed 12/24/2004. - -

is inserted as **Line 1** above the subtitle of "Technical Field".

7. On **Page 1** of the Specification, the header "DESCRIPTION" is deleted.

REJOINDER

8. Claims 70, 72-76 are allowable. Claims 30-31, 40-45, previously withdrawn from consideration as a result of a restriction requirement, require all the limitations of an allowable claim. Pursuant to the procedures set forth in MPEP § 821.04(a), **the restriction requirement among inventions I-VIII, as set forth in the Office action mailed on December 19th, 2008, is hereby withdrawn** and claims 30-31, 40-45 are hereby rejoined and fully examined for patentability under 37 CFR 1.104. In view of the withdrawal of the restriction requirement, applicant(s) are advised that if any claim presented in a continuation or divisional application is anticipated by, or includes all the limitations of, a claim that is allowable in the present application, such claim may be subject to provisional statutory and/or nonstatutory double patenting rejections over the claims of the instant application. Once the restriction requirement is withdrawn, the provisions of 35 U.S.C. 121 are no longer applicable. See *In re Ziegler*, 443 F.2d 1211, 1215, 170 USPQ 129, 131-32 (CCPA 1971). See also MPEP § 804.01.

REASONS FOR ALLOWANCE

9. The following is an examiner's statement of reasons for allowance.

The closest cited prior art of record, US 2002/0018886, fails to fairly teach or suggest, even in view of US 7,229,686, US 4,692,492 and US 2003/0077437, an antireflection film comprising the specific combination of: a transparent support; and a low-refractive index layer having a lower refractive index than the transparent support, wherein the low-refractive index layer is an outermost layer of the antireflection film, and the low-refractive index layer comprises: a hollow silica particle; and a compound lowering a surface free energy of the antireflection film, wherein a silicone is segregated at an outer surface of the low-refractive index layer such that a spectral intensity ratio Si/C in a photoelectron spectrum at the outer surface is larger by at least 5 times than that at a depth from the outer surface, the depth being equal to 80 % of a thickness of the low-refractive index layer, wherein the compound is a silicone compound having a plurality of (meth)acryloyl groups at a terminal or a side chain of a compound chain that contains a plurality of dimethylsilyloxy units as repetitive units, and having a molecular weight of from 3,000 to 30,000, wherein the low-refractive index layer comprises a binder, and the compound comprises a reactive group with the binder, wherein the binder consists of a (co)polymer of at least one monomer having two or more ethylenic unsaturated groups, wherein the monomer having two or more ethylenic unsaturated groups consists of ethylene glycol di(meth)acrylate, 1,4-cyclohexane diacrylate, pentaerythritol tetra(meth)acrylate, pentaerythritol tri(meth)acrylate, trimethylolpropane tri(meth)acrylate, trimethylolethane tri(meth)acrylate, dipentaerythritol

tetra(meth)acrylate, dipentaerythritol penta(meth)acrylate, dipentaerythritol hexa(meth)acrylate, 1,2,3-cyclohexane tetramethacrylate, polyurethane polyacrylate, polyester polyacrylate, or a combination thereof, wherein the hollow silica particle has a porosity x of from 10 to 60%, the porosity being represented by the following formula (V):

$$x = (4\pi a^3/3)/(4\pi b^3/3) \times 100 \quad (V)$$

wherein a represents a radius of a hollow of the particle and b represents a radius of an outer shell of the particle.

See Applicant's remarks dated 05/17/11. Furthermore, see the comparative data where Applicant's working examples show unexpectedly superior results in terms of the overall combination of low mean specular reflectivity, low mean integral reflection, low surface free energy, good rubber eraser friction resistance, good felt pen wiping performance, high steel wool scratch resistance and high adhesiveness (Tables 4-6 of Applicant's specification).

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication should be directed to Sow-Fun Hon whose telephone number (571)272-1492. The examiner can normally be reached Monday to Friday from 10:00 AM to 6:00 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Angela Ortiz, can be reached at (571)272-1206. The fax phone number for the organization where this application or proceeding is assigned is (571)273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

/Sophie Hon/

Sow-Fun Hon

Primary Examiner, Art Unit 1798